

Ring magnetron



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The annular magnetron is designed for sputtering targets made of conductive materials in a vacuum.

Parameter	Value
Maximum power	5000 W
Maximum current	10 A
Target inner diameter	237 mm
Target height	40 mm
Target thickness	4 mm
Device weight no more	6,6 kg
Chamber working pressure range	0,01-10 Pa

Any working gas that does not cause deposition of high-resistance layers on the parts of the device

Working fluid (recommended) distilled water

Minimum coolant consumption, no more, l / min

at working power, kW: 2 l / min at 3KW;

7 l / min at 4KW;

12 l / min at 5KW;

There are special designs for different applications.

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basic dimensions, versions, structure

Main elements

- 1 - body;
- 2 - plate;;
- 3 - insulator;
- 4 - magnetic circuit;
- 5 - target holder;
- 6 - external magnets;
- 7 - internal magnets;
- 8 - clamp;
- 9 - target;;
- 10 - screen.

